

T. Rohe et al. 7th RD50 Workshop Nov. 14-16, 2005, CERN

Pixel Devices on the common RD50 n-in-p Strip Detector Mask Set (200mm)

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7th RD50 workshop, Nov 14-16, 2005, CERN



Motivation

- "n-in-p" pixel sensors very attractive
 - Single sided process (cheap)
 - Potentially the same radiation hardness as "n-in-n"
- 200mm mask set dedicated to strip detectors
 See next talk by Hartmut
- Pixel devices are "parasitic"
 - Cover only a small fraction of the wafer
 - Only "single-chip"-devices are included
 - They contain (almost) all features of full size detectors
 - Should not make additional demands on the technology (which cost money)



Implications for Pixels

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- Process contains a poly layer
 - not necessary for DC-coupled pixels
 - some "experimental" structures use it as field plates in the pixel
- No passivation
 - problematic for bump bonding ?!!!
 - reconsider passivation ??
- Probably no bump deposition on wafer level
 - Limits possible bump vendors
 - Expensive
 - Small number of devices (costs not so important?)





Summary of Devices

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- "ATLAS"-type (1 flavour)
 - Size $9.8 \times 10.4 \text{ mm}^2$
 - Array 18 \times 160(+4) pixels
 - Pitch 400 \times 50 μm^2 (edge: 600 μm)
- "CMS"-type (2 flavours, w and w/o poly)
 - Size $9.9 \times 10.2 \text{ mm}^2$
 - Array 52 \times 80 pixels
 - Pitch $(150 \times 100 \ \mu m^2)$ (edge: double)
- "PSI" type (2 flavours, w and w/o poly)
 - Size $5.4 \times 6.2 \text{ mm}^2$
 - Array 22 \times 40 pixels
 - Pitch $(150 \times 100 \ \mu m^2)$ (edge: double)

Pixel Cell w/o Poly

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• ATLAS

- Original dimensions
 - very narrow bias dot
- Width of moderated region increased to 7µm
- Bump pad marked with via

• CMS

- Gap slightly increased $20 \rightarrow 30 \mu m$
- Width of moderated region increased to $10 \mu m$
- Bias dot much larger than original



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Pixel with Poly

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- Poly provided by strip technology
- Use it as field plate
 - higher breakdown voltage ?
 - problems at the point crossing the metal
- Not (easily) possible in ALTAS geometry because of small pitch







Edge Pixels

CMS

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• ATLAS

- last 200 μ m not covered by ROC
- 4 pixels are connected to others
- pixel in other direction are elongated

- last 100µm not covered by ROC
- Edge pixels are elongated in both directions



Guard Rings



- Bias ring ~50µm
- 10 guard rings with in increasing pitch
 - not optimised for p-spray isolated n-side
 - gap filled with "low dose" p-spray
- High bias at device edge problematic?



Summary

- "n-in-p" pixel sensors for inclusion on the common RD50 200mm-wafer drawn (will be submitted to Gianluigi this week)
- Sensors are compatible with
 - ATLAS ROC (FE-I)
 - CMS ROC (PSI 46)
 - Generic pixel chip (PSI 49)
- Design close to such used in LHC experiments
- Additional design using poly field plates
 - Potentially higher breakdown voltage
 - Not standard for DC-coupled pixel
 - 2 extra mask layers (costs)





Open Questions

- Bump bonding
 - Single die bump bonding
 - No passivation
 - Possible vendors
 - PSI ? (Only limited resources available. Overview of all wishes by RD50 very helpful)
 - IZM ?? (ATLAS institutes and other non-RD50 members interested??)
 - Others???
 - Availability of readout chips?
 - Funding?
- Who will test the devices?
 - Complicated infrastructure necessary to run readout chips: Source (beta, gamma), laser?
 - Test beam as part of experiments (ATLAS/CMS/...)?
 - Irradiation: probably CERN-PS